

SEMICONDUCTOR STRUCTURE, METHOD FOR FORMING SAME AND LAYOUT STRUCTURE

ABSTRACT

Embodiments of the disclosure provide a semiconductor structure, a method for forming same and a layout structure. The method comprises: providing a substrate, which includes a first area and a second area arranged in sequence in a second direction, in which the first area includes active layers arranged at intervals in a third direction; forming an initial gate structure located on a surface of each active layer in the first area; etching the initial gate structures to form comb-shaped gate structures stacked in a third direction, in which each comb-shaped gate structure at least includes first gate structures arranged at intervals in the first direction, the first, second and third directions are perpendicular to one another, and the first and second directions are parallel to a surface of the substrate; and forming bit line structures extending in the third direction and capacitor structures extending in the second direction in the second area, in which the bit line structures and the capacitor structures are connected to the first gate structures.

[Fig. 1]